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SHIMAZU et al

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U.S. PATENT DOCUMENTS EXAMINER FILING DATE DOCUMENT NUMBER DATE NAME CLASS SUBCLASS 5 9 3 4/99 Wu 6 2 9 4 4 2 0 9/01 Tsu FOREIGN PATENT DOCUMENTS DOCUMENT NUMBER DATE COUNTRY CLASS SUBCLASS TRANSLATION YES NO 2 8 6 0 6 2 1/91 Germany 9 4 7 5 5/97 9 1 3 Japan 2 3 6 11/91 8 5 4 Japan 6 2 9 2 8 8 2/94 Japan 60 2 1 3 0 5 8 10/85 Japan 1 6 7 3 5 7/91 6 Japan OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) Mo et al "Formation and Properties of Ternary Silicide (CoNi)Si2 Thin Films, IEEE 1998 5th

International Conference on Solid State And Integrated Circuit Technology pp 271-274 Hong et al "Magneto-Optic Kerr Effect Measurements on FeCoSi Epitaxially Stabilized on Si (111), Journal of Magnetism and Magnetic Materials, vol. 165 pp 212-215

> http://www.puretechnic.com and http://tosohsmd.com/tsprod.tspcobdt.htm, Material Data Sheet MDS 27.000 which jncludes the total metallics of the cobalt target, pp 1-4 and 1-3

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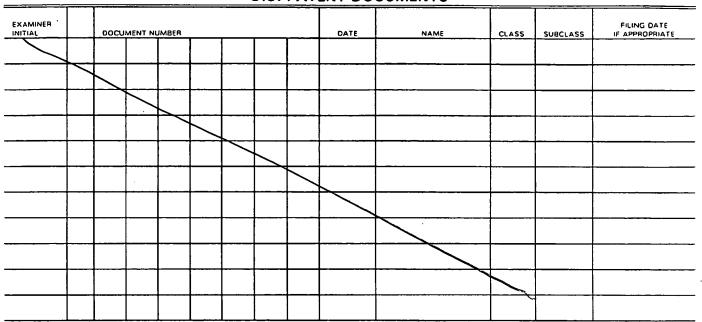
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FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							4/95	Japan			ABS	NO
7	1	0	6	2	8	0						
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

i	Physical Review Letters, Vol. 78, No. 16 (April 1997) pp 3133-3136; full text							
(A)	Handbook on Thin Filter Manufacturing Method, Japan, Kyoritsu Shuppan KK (10/94) pp 321-322. "A Metal Silicide"							
(00	Physical Review Letters, Vol. 50, No. 6 (Feb. `983), pp. 429-432 full t. xt							

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FOREIGN PATENT DOCUMENTS CLASS COUNTRY SUBCLASS TRANSLATION DOCUMENT NUMBER DATE YES NO

Safety and Health Guide For The Microelectronics Industry, Hazard Communication, OSHA 310, pp 9, 1998

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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